PACE TECHNOLOGIES
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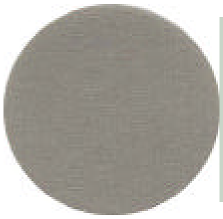
Polishing Pad Selection Guide

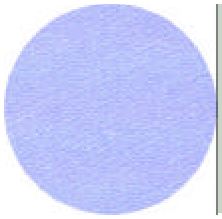


Metal Mesh Cloth is a wire mesh material used for coarse and intermediate (15 µm or 30 µm diamond) lapping / polishing. The texture and spacing of the wire mesh allows for the abrasive to become semi-fixed; thus offering the advantage of increased stock removal, while minimizing damage. It is particularly useful for ceramics and composites.

POLYPAD™ Polishing Cloth is a synthetic polyester polishing pad which has a similar polishing action to a nylon pad, with the exception that it is more durable. It is used for the intermediate diamond polishing steps using 3,6,9 or 15 µm polycrystalline diamond.

TEXPAN™ Polishing Cloth is the most commonly used low napped polymer polishing pad. Its primary applications are as an intermediate polishing pad (3,6 or 9 µm diamond) for metals and as both an intermediate and final polishing pad for hard ceramics and composites (1, 3 or 6 µm diamond).

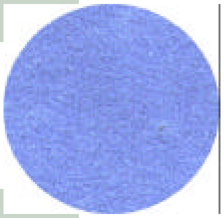
Black Chem™ Polishing Cloth is a porometric polymer pad which has a low nap but behaves as an intermediate polishing pad with a performance between TEXPAN™ pad and POLYPAD™ cloth. It is useful for materials such as silicon or glass which are too brittle for TEXPAN™ pad and too hard for POLYPAD™ cloth.



DACRON® Polishing Cloth is a low napped polishing pad for polishing primarily with 1-15 micron diamond abrasives. The DACRON pad is the most popular intermediate polishing pad in Europe and is used mostly for polishing metals.

Note: DACRON is a registered trade name of DUPONT Corporation.

NEW!



NEW!

TRICOTE™ Polishing Cloth - this is a tightly woven suede final polishing pad for metals and polymers. This cloth is very popular for final polishing with alumina and colloidal silica, especially for plated and coated specimens where edge retention is critical.

NAPPAD™ Polishing Cloth is a very high napped final polishing pad useful for most metals and polymers. Its high nap provides a soft and gentle polishing action. Common abrasives used with NAPPAD™ cloth are 0.05 µm nanometer alumina and SIAMAT™ colloidal silica.

MICROPAD™ Polishing Cloth has been the most commonly used pad for final polishing of metals and polymers. Its high nap provides a soft and gentle polishing action. Common abrasives used with MICROPAD™ cloth are 0.05 µm nanometer alumina and SIAMAT™ colloidal silica.

MICROPAD™ Extra Polishing Cloth is very similar to MICROPAD™ , however it is a much more durable polishing pad. Its primary application is for final polishing of metals and polymers. Its high nap provides a soft and gentle polishing action. Common abrasives used with MICROPAD™ Extra cloth are 0.05 µm nanometer alumina and SIAMAT™ colloidal silica.

NEW!

MOLTEC™ Polishing Pad - This is a wool polishing cloth used for final polishing and has a very high nap. It is most commonly used for final polishing metals where edge retention is a minimal consideration

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POLISHING PAD GUIDELINE

Process Step	Planar Grinding	Rough Polishing	Final Polishing
Hard/ tough ceramics	CERMESH	TEXPAN or POLYPAD	TEXPAN or DACRON📥
Brittle ceramics (silicon chips, glass, etc.)	CERMESH	Black Chem or DACRON📥	TEXPAN or DACRON📥
Hard metals	SiC paper	TEXPAN 🌶 POLYPAD 🌶	MICROPAD Extra, MICROPAD or TRICOTE
Soft metals	SiC paper	TEXPAN or NYPAD™ or DACRON📥	MICROPAD Extra, NAPPAD or MOLTEC
Polymers	SiC paper	TEXPAN	NAPPAD
Abrasive	**SiC or coarse diamond**	**Polycrystalline diamond**	**Alumina or colloidal silica**

METAL MESH ABRASIVE CLOTH (w/PSA)

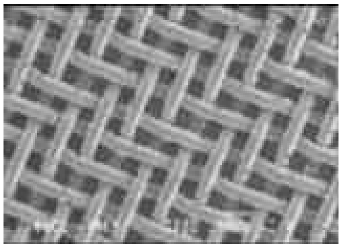
Description	Diameter (inches)	Quantity	Catalog Number
CERMESH™ Cloth	8	5/pkg	CMESH-2008
CERMESH™ Cloth	10	5/pkg	CMESH-2010
CERMESH™ Cloth	12	5/pkg	CMESH-2012

LOW NAPPED (Rough Polishing) CLOTH (w/PSA)

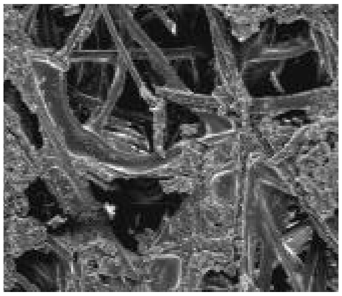
Description	Diameter (inches)	Quantity	Catalog Number
DACRON® Pad	8	5/pkg	DC-3008
DACRON® Pad	10	5/pkg	DC-3010
DACRON® Pad	12	5/pkg	DC-3012
TEXPAN™ Pad	8	10/pkg	TP-5008
TEXPAN™ Pad	10	10/pkg	TP-5010
TEXPAN™ Pad	12	10/pkg	TP-5012
POLYPAD™ Pad	8	10/pkg	PP-6008
POLYPAD™ Pad	10	10/pkg	PP-6010
POLYPAD™ Pad	12	10/pkg	PP-6012
Black CHEM™ Pad	8	10/pkg	BC-8008
Black CHEM™ Pad	10	10/pkg	BC-8010
Black CHEM™ Pad	12	10/pkg	BC-8012

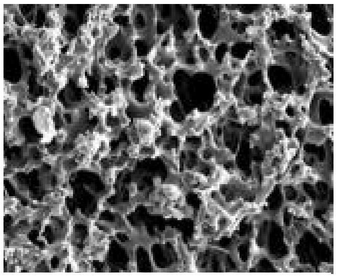
HIGH NAPPED (Final Polishing) CLOTH (w/PSA)

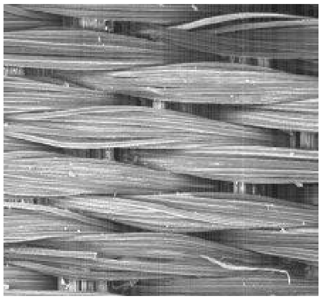
Description	Diameter (inches)	Quantity	Part Number
NAPPAD™ Pad	8	10/pkg	NP-7008
NAPPAD™ Pad	10	10/pkg	NP-7010
NAPPAD™ Pad	12	10/pkg	NP-7012
MICROPAD™ Pad	8	10/pkg	MP-9008
MICROPAD™ Pad	10	10/pkg	MP-9010
MICROPAD™ Pad	12	10/pkg	MP-9012
MICROPAD™ Extra	8	10/pkg	MPE-9008
MICROPAD™ Extra	10	10/pkg	MPE-9010
MICROPAD™ Extra	12	10/pkg	MPE-9012
TRICOTE™	8	10/pkg	TRI-4008
TRICOTE™	10	10/pkg	TRI-4010
TRICOTE™	12	10/pkg	TRI-4012
MOLTEC™	8	10/pkg	MT-7008
MOLTEC™	10	10/pkg	MT-7010
MOLTEC™	12	10/pkg	MT-7012

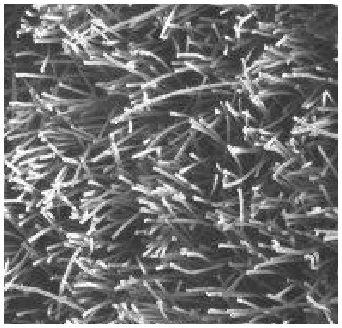

CERMESH™ metal mesh cloth

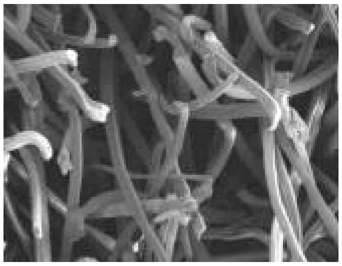

POLYPAD™ pad

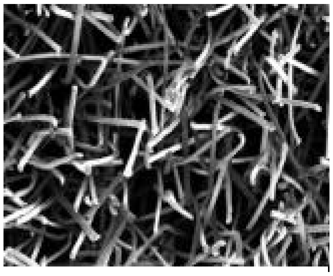


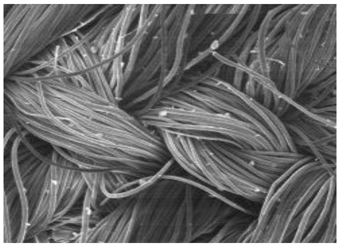

Black Chem™ pad


DACRON® pad


TRICOTE™ pad


High napped pad (MICROPAD™ Extra, MICROPAD™, CYPAD™)


NAPPAD™ pad


MOLTEC™ pad

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